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TA A	Application No.	Applicant(s)
Notice of Allowability	0/817,030	VAN DUN ET AL.
	xaminer	Art Unit
	lathan M. Nutter	1711
The MAILING DATE of this communication appears All claims being allowable, PROSECUTION ON THE MERITS IS (O serewith (or previously mailed), a Notice of Allowance (PTOL-85) or NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGH of the Office or upon petition by the applicant. See 37 CFR 1.313 ar	R REMAINS) CLOSED in this ap other appropriate communication HTS. This application is subject t	plication. If not included n will be mailed in due course. THIS
. This communication is responsive to 18 July 2005.		
2. The allowed claim(s) is/are <u>55-80,83 and 84.</u>		
a) Acknowledgment is made of a claim for foreign priority under a) All b) Some* c) None of the: 1. Certified copies of the priority documents have be 2. Certified copies of the priority documents have be 3. Copies of the certified copies of the priority documents have be 3. Copies of the certified copies of the priority document international Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMENTHIS THREE-MONTH PERIOD IS NOT EXTENDABLE. A SUBSTITUTE OATH OR DECLARATION must be submitted INFORMAL PATENT APPLICATION (PTO-152) which gives a complete including changes required by the Notice of Draftsperson 1) hereto or 2) to Paper No./Mail Date	een received. een received in Application No ments have been received in this this communication to file a reply NT of this application. ed. Note the attached EXAMINER reason(s) why the oath or declar oe submitted. o's Patent Drawing Review (PTO mendment / Comment or in the of (c)) should be written on the drawing	national stage application from the complying with the requirements R'S AMENDMENT or NOTICE OF ation is deficient. -948) attached Office action of the front (not the back) of
each sheet. Replacement sheet(s) should be labeled as such in the . DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT FO	of BIOLOGICAL MATERIAL	must be submitted. Note the
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Attachment(s)		
I. ☐ Notice of References Cited (PTO-892)	5. Notice of Informal I	Patent Application (PTO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary	
 Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No./Mail Date <u>07-05</u> 	Paper No./Mail Da , 7. ☐ Examiner's Amend	ment/Comment
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. ⊠ Examiner's Statem 9. □ Other	ent of Reasons for Allowance

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REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance: no prior art has been found that either teaches or fairly suggests the production of a polyethylene composition comprising a "low-molecular-weight (LMW) ethylene homopolymer component and a high-molecular-weight (HMW) ethylene interpolymer component, and wherein the LMW component has a molecular weight distribution, MWD^L, of less than about 8, and wherein the HMW component has a molecular weight distribution, MWD^H, less than about 5 and has a substantially uniform comonomer distribution, or wherein the HMW component has a reverse comonomer distribution.," as recited in claim 55. Further, no prior art has been found that either teaches or fairly suggests the production of a polyethylene composition comprising "a low-molecular-weight (LMW) ethylene homopolymer component, and a high-molecular-weight (HMW) ethylene interpolmer component, and wherein the LMW component has a molecular weight distribution, MWD^L, of less than about 8, and wherein the same catalyst system is used to make the LMW component and the HMW component, and wherein the composition has a molecular weight distribution less than 17.5." Further, no prior art has been found that either teaches or fairly suggests the production of a polyethylene composition comprising "a low-molecular-weight (LMW) ethylene homopolmer component, and a high-molecular-weight (HMW) ethylene interpolymer component, and wherein the LMW component is chacterized as having a molecular weight distribution, MWDL, of less than about 8, and wherein the LMW component is prepared from a constrained geometry catalyst." The references to Bailey et al (US 4,461,873), Martin et al (US 5,319,029),

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Rohde et al (US 6,462,135) and de Lange et al (US 6,545,093) fail to teach or suggest the instantly claimed invention for the reasons stated in the "Response to the Office Action dated 18 April 2005." Since there are no other outstanding issues with regard to the clarity or enablement of the claims, these claims are deemed to contain allowable subject matter.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nathan M. Nutter whose telephone number is 571-272-1076. The examiner can normally be reached on 9:30 a.m.-6:00 p.m..

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, James J. Seidleck can be reached on 571-272-1078. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

Nathan M. Nutter Primary Examiner

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28 September 2005